

ABSTRACT

An object of the present invention is to provide a sintered alloy having high mechanical strength (specifically, high toughness suitable for a sputtering target material) and a sputtering target material including the sintered alloy, and the present invention provides a sintered alloy that includes: Mn; an A-group element consisting of one or more of Ga, Zn, Sn, Ge, Al, and Co; and optionally a B-group element consisting of one or more of Fe, Ni, Cu, Ti, V, Cr, Si, Y, Zr, Nb, Mo, Ru, Rh, Pd, Ag, In, Ta, W, Re, Ir, Pt, Au, Bi, La, Ce, Nd, Sm, Gd, Tb, Dy, and Ho, wherein the balance is an inevitable impurity, wherein the sintered alloy includes one or more of a 1st to a 6th Mn phases that satisfy predetermined conditions.